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FORM PTO-1449 (modified)  
To: U.S. Department of Commerce  
(PW FORM PAT-1449)  
Patent and Trademark Office

Atty.  
Dkt. No.

M#

Client Ref.

308089

P-01500.010-US

# INFORMATION DISCLOSURE STATEMENT BY APPLICANT

Applicant: FLAGELLO et al.

Continuation-In-Part of Appln. No.: 10/374,509 filed  
February 27, 2003 10/786, 473

Filing Date: February 26, 2004

Date: February 26, 2004

Page

1

of

2

Examiner: Unassigned

Group Art Unit: Unassigned

## U.S. PATENT DOCUMENTS

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
PA	AR 3,998,524	12/1976	HUBBY, Jr. et al.			
PA	BR 4,384,760	05/1983	ALFERNES			
PA	CR 5,383,053	01/1995	HEGG et al.			
PA	DR 6,288,840	09/2001	PERKINS et al.			
PA	ER 6,392,800	05/2002	SCHUSTER			
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PA	GR 6,122,103	09/2000	PERKINS et al.			
PA	HR 6,191,880 B1	02/2001	SCHUSTER			
PA	IR 5,523,193	06/1996	NELSON			
PA	JR 5,296,891	03/1994	VOGT et al.			
PA	KR 5,229,872	07/1993	MUMOLA			
PA	LR 6,046,792	04/2000	VAN DER WERF et al.			

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Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract	Translation Readily Available
				Enclosed	No
MR 98/38597	09/1998	WIPO	Thuren		
NR 98/33096	07/1998	WIPO	Sandstrom et al.		

## OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

PA	OR	Flagello et al., "Theory of high-NA imaging in homogeneous thin films," <i>J. Opt. Soc. Am. A</i> 13(1):53-64 (1996)			
PA	PR	Lopez et al., "Wave-plate polarizing beam splitter based on a form-birefringent multilayer grating," <i>Optics Letters</i> 23(20):1627-1629 (1998)			
PA	QR	Ferstl et al., "High-frequency gratings as polarization elements," <i>Part of the SPIE Conference on Micromachine Technology for Diffractive and Holographic Optics</i> 2879:138-146 (1999)			
PA	RR	Flagello et al., "Optical Lithography into the Millenium: Sensitivity to Aberrations, Vibration and Polarization," <i>SPIE The 25<sup>th</sup> Annual International Symposium on Microlithography</i> , February 27-March 3, 2000, Santa Clara, CA, pp. 1-12			
PA	SR	Switkes et al., "Immersion lithography at 157 nm," <i>J. Vac. Sci. Technol. B</i> 19(6):2353-2356 (2001)			
PA	TR	Bomzon et al., "Radially and azimuthally polarized beams generated by space-variant dielectric subwavelength gratings," <i>Optics Letters</i> 27(5):285-287 (2002)			
PA	UR	Mulkens et al., "157-nm Technology: Where are we Today?," <i>SPIE The 27<sup>th</sup> Annual Symposium on Microlithography</i> , March 3-8, 2002, Santa Clara, CA, pp. 1-11			

Examiner

Date Considered:

12-12-05

\*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

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Page

2

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Group Art Unit: Unassigned

## U.S. PATENT DOCUMENTS

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
<i>PJ</i>	AR 6,288,840 B1	09/2001	PERKINS et al.			
<i>PJ</i>	BR 6,262,796 B1	07/2001	LOOPSTRA et al.			
<i>PJ</i>	CR 5,969,441	10/1999	LOOPSTRA et al.			
	DR					
	ER					
	FR					
	GR					
	HR					
	IR					
	JR					
	KR					
	LR					
	MR					
	NR					
	OR					

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						Enclosed	No	Enclose	No
	PR								
	QR								
	RR								
	SR								
	TR								
	UR								

## OTHER (Including in this order: Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

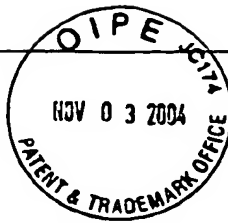
	VR						
	WR						
	XR						
	YR						
	ZR						
	AAR						
	BBR						
	CCR						

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Applicant: FLAGELLO et al.	
Application No.: 10/786,473	
Filing Date: February 26, 2004	
Examiner: Unassigned	Group Art Unit: 2872

Date: November 3, 2004 Page 1 of 1

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	IR						
	JR						
	KR						
	LR						

**FOREIGN PATENT DOCUMENTS**

FOREIGN PATENT DOCUMENTS							English Abstract		Translation Readily Available	
		Document Number	Date MM/YYYY	Country	Inventor Name					
							Enclosed	No	Enclose	No
PA	MR	196 21 512 A1	12/1997	DE	Kley et al.		x			
	NR									

**OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)**

PA	OR	B. Stenkemp et al., "Grid polarizer for the visible spectral region," SPIE, p. 288-296, 1994.								
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